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IMS NANOFABRICATION ANNOUNCES EQUITY FUNDING ROUND WITH INTEL CAPITAL AND PHOTRONICS

VIENNA, AUSTRIA (DECEMBER 7, 2011) – IMS Nanofabrication AG (www.ims.co.at), an innovator in nanometer scale mask and direct write lithography imaging technology for semiconductor manufacturing applications, today announced that it has signed an equity funding round with participation from Intel Capital, Photronics Inc. and private investor groups.

“We are pleased to announce the funding support being provided by Intel Capital, Photronics and our existing investor groups as we work to commercialize our electron multi-beam mask exposure tool (eMET) for sub 22nm mask writing applications,” said Max Bayerl, CEO of IMS. “The additional resources will help IMS to demonstrate a 256 thousand e-beam mask writer column with initial exposures by the end of 2011.” Technical feasibility for the eMET platform concept was established via work completed under a proof of writing strategy (POWS) program completed earlier in 2011.

“Intel Capital is pleased to support the innovation in electron multi-beam patterning being driven by IMS,” said Keith Larson, vice president, Intel Capital. “Successful demonstration of an electron multi-beam mask writer column would be a significant step forward in addressing industry needs for higher productivity mask writing capability at finer levels of resolution.”

Photronics is joining the equity round to support the development of technology that allows it to provide leading edge mask production capability to its customers. Christopher Progler, Chief Technology Officer, Photronics, said, “Our investment in IMS demonstrates our commitment to invest in technologies that can keep Photronics on the cutting edge of mask writing technology.”

The equity funding will be used to complete an electron multi-beam mask exposure tool proof-of-concept (eMET POC) to support tool characterization, column optimization and infrastructure enhancements that set the stage for commercialization. Additional terms of the transaction are not being disclosed. The equity funding agreement is subject to satisfaction of customary closing conditions with closing expected to occur by the end of 2011.

About IMS

IMS Nanofabrication AG (“IMS”) is an Austrian based high-tech company that was founded in December 2006 through the merger of the former IMS Nanofabrication GmbH and IMS - Ionen Mikrofabrikations Systeme GmbH. Based on its extensive know-how in charged particle systems, IMS offers solutions to directly transfer custom designed patterns to resist or to generate resist-less two and three dimensional surface modifications with

features below 20 nanometers. IMS focuses its efforts on the development and production of key tool components for mask writing and direct write lithography applications. It plans to commercialize its technology and related services in cooperation with the strategic investors participating in this funding round and with other parties involved in the mask and lithography ecosystem. For more information on IMS Nanofabrication AG, visit www.ims.co.at.

About Intel Capital

Intel Capital, Intel's global investment and M&A organization, makes equity investments in innovative technology start-ups and companies worldwide. Intel Capital invests in a broad range of companies offering hardware, software, and services targeting enterprise, mobility, health, consumer Internet, digital media, semiconductor manufacturing and cleantech. Since 1991, Intel Capital has invested more than US\$10.4 billion in over 1,185 companies in 51 countries. In that timeframe, 194 portfolio companies have gone public on various exchanges around the world and 286 were acquired or participated in a merger. In 2010, Intel Capital invested US\$327 million in 119 investments with approximately 44 percent of funds invested outside the U.S. and Canada. For more information on Intel Capital and its differentiated advantages, visit www.intelcapital.com.

About Photronics, Inc.

Photronics is a leading worldwide manufacturer of photomasks. Photomasks are high precision quartz plates that contain microscopic images of electronic circuits. A key element in the manufacture of semiconductors and flat panel displays, photomasks are used to transfer circuit patterns onto semiconductor wafers and flat panel substrates during the fabrication of integrated circuits, a variety of flat panel displays and, to a lesser extent, other types of electrical and optical components. They are produced in accordance with product designs provided by customers at strategically located manufacturing facilities in Asia, Europe, and North America. Additional information on the Company can be accessed at www.photronics.com.